

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. : 10/040,042
Applicant : Wei-Yu Su
Filed : November 7, 2001
TC/A.U. : 1746
Confirmation No. : 1835
Title : Method for Reduction of Photomask Defects
Examiner : El Arini, Zeinab
Attorney Docket No : N1085-90003
Customer No. : 08933

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT AND RESPONSE UNDER 37 CFR 1.116(a)

In response to the Office Action of October 3, 2006, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 7 of this paper.